

## Supporting information

### Experimental Section

**Sample preparation and characterization:** Ultrathin SnS<sub>2</sub> nanosheets were synthesized via CVD in a horizontal vacuum furnace tube. To grow SnS<sub>2</sub> nanosheets, Sn granules (1 g, Aldrich) were placed in a quartz boat at the center of furnace, and sulfur powder (0.8 g, Aldrich) was placed in another quartz boat upstream in the furnace. Segments of a 300 nm SiO<sub>2</sub>/Si wafer were placed face up in a quartz boat downstream of the sources. Prior to growth, the tube was cleaned by high-purity Ar at a rate of 300 standard cubic centimeter per minute (sccm) for 10 minutes to eliminate oxygen in the furnace. After flushing the tube with high-purity Ar three times and pumping to 30 mtorr, the furnace was heated to 700 °C in 20 minutes and kept at this temperature for 45 minutes. During the growth process, high-purity Ar with a flow rate of 60 sccm was used as the carrier gas. Finally, the furnace was naturally cooled to room temperature and the ultrathin SnS<sub>2</sub> nanosheets formed on the 300 nm SiO<sub>2</sub>/Si substrates were recovered. The optical images and SEM images of SnS<sub>2</sub> were obtained using a Shanghai 9XB-PC microscope and SEM (Cari Zeiss). The thicknesses were measured using Seiko SPI3800N AFM. The Raman spectra of the synthesized SnS<sub>2</sub> were measured using Renishaw 2000 confocal Raman system. The crystal structural characterization was performed by transmission electron microscope

(TEM, JEOL-TEM).

**Device fabrication and measurements:** SnS<sub>2</sub>-based devices were fabricated using UV lithography and silver wires shadow mask methods, and Ti/Au (10 nm/100 nm) metal electrodes were deposited by electron beam evaporation. The electronics, optoelectronics and gas sensing data were collected using a Keithley 2400. Several Laser diodes were used as light sources for measurements of the light response under ambient conditions. To measure the gas response, the SnS<sub>2</sub>-based gas sensors were sealed in a transparent chamber and partial flows NO<sub>2</sub> and N<sub>2</sub> gas were alternately introduced, with a total flow velocity 200 sccm. Before each measurement, the chamber was pumped to a vacuum state for more than 1 hour to desorb contaminant molecules and regenerate the surface, then pure dry N<sub>2</sub> was injected for more than 1 hour to stabilize the original state for NO<sub>2</sub> testing in a N<sub>2</sub> background. The pressure of chamber was kept at standard atmospheric pressure.

**DFT simulation:**

Calculations of the electronic structure of a SnS<sub>2</sub> monolayer with an adsorbed NO<sub>2</sub> molecule was performed using the density functional theory (DFT) implemented in the VASP package<sup>[1, 2]</sup>. The VASP package utilizes the projector augmented wave (PAW) method. The exchange and correlation energies used the Perdew-Burke-Ernzerhof (PBE) functional with the generalized gradient approximation (GGA)<sup>[1, 2]</sup>. The energy cutoff for the plane-wave basis expansion was set to 350

eV and an energy convergence criteria of  $1 \times 10^{-5}$  eV per unit cell was chosen. A  $12 \times 12 \times 1$  k-grid mesh was used to sample the Brillouin zone. Initially, we used the experimental lattice parameters of bulk  $\text{SnS}_2$ <sup>[3]</sup> to construct the  $\text{SnS}_2$  monolayer. We fixed the in-plane lattice constant and optimized all the atoms in the supercell. The residual force and stress were less than 0.01 eV/Å and 1.0 kBar, respectively. The vacuum thickness of supercell was above 15Å. For the  $\text{SnS}_2$  adsorption of a  $\text{NO}_2$  molecule, the van der Waals force correction<sup>[4]</sup> was adopted to optimize the lattice structural parameters and bond length. The spin polarization calculation also was adopted to calculate the binding energy and electrical conductivity, due to the  $\text{NO}_2$  is polar molecule. We constructed a  $3 \times 3 \times 1$   $\text{SnS}_2$  monolayer supercell to connect with a  $\text{NO}_2$  molecule, of the type  $\text{Sn}_9\text{S}_{18}$  which contain 9 Sn atoms and 18 S atoms. Also, another  $3 \times 3 \times 1$   $\text{SnS}_2$  monolayer supercell with one S vacancy named of the stoichiometry  $\text{Sn}_9\text{S}_{17}$ . The adsorption energy calculation result is based on the above described supercell. The N-O bonds point down to the  $\text{SnS}_2$  monolayer which implies the O atom is located between the N and S atoms. For brevity, in the present study, we only calculated the N-O bonds pointing down towards the  $\text{SnS}_2$  monolayer shown in Fig. 7(a). The electron conductivity was calculated as a function of the chemical potential  $\mu$  for the temperature  $T = 300\text{K}$ . All of the calculation results were obtained by the wannier90 code within BoltzWann module<sup>[5, 6]</sup>. Initially, starting the  $12 \times 12 \times 1$  grid for the construction of the Wannier function and using the dense  $80 \times 80 \times 1$  mesh to calculate the BoltzWann module. The VESTA package was used to draw the

charge density difference of SnS<sub>2</sub> monolayer adsorbing a NO<sub>2</sub> molecule, and with S vacancy<sup>[7]</sup>.

### Formula 1

#### The calculation of mobility

we can estimate the mobility of the SnS<sub>2</sub> using the following equation:

$$\mu = \frac{dI_{DS}}{dV_G} \cdot \frac{L}{WC_{SiO_2}V_{DS}}$$

where  $L=45.5 \mu\text{m}$  and  $W=32.7 \mu\text{m}$  are the length and width of the conduction channel, respectively, and  $C_{SiO_2} = \epsilon_0\epsilon_r/d$  is capacitance per unit area estimated for the gate dielectric, with  $\epsilon_0$  being the free-space permittivity,  $\epsilon_r=3.9$  is the relative permittivity for SiO<sub>2</sub>, and  $d=300 \text{ nm}$  is the thickness of the SiO<sub>2</sub>. The calculated  $C_{SiO_2}$  for 300 nm thick SiO<sub>2</sub> is  $\approx 1.6 \text{ nF/cm}^2$  and the calculated mobility is  $\mu=9.7 \text{ cm}^2/\text{Vs}$ .

### Formula 2

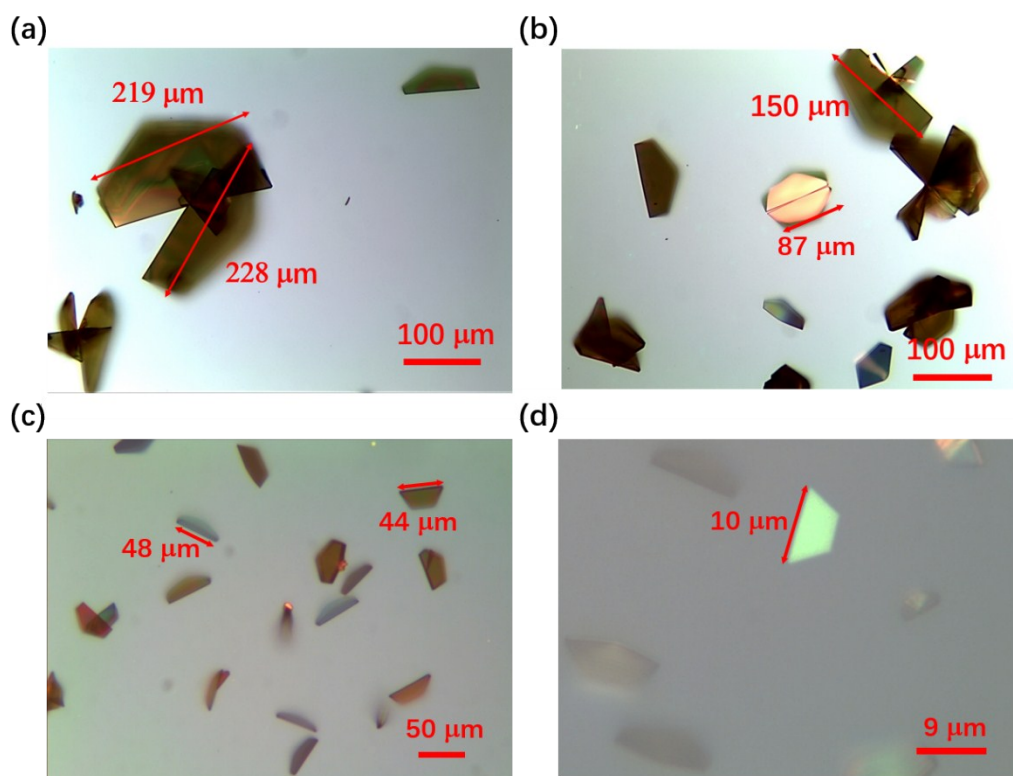
#### The calculation of responsivity and external quantum efficiency

The responsivity ( $R_\lambda$ ) and external quantum efficiency (EQE) can be calculated by the following relationships:

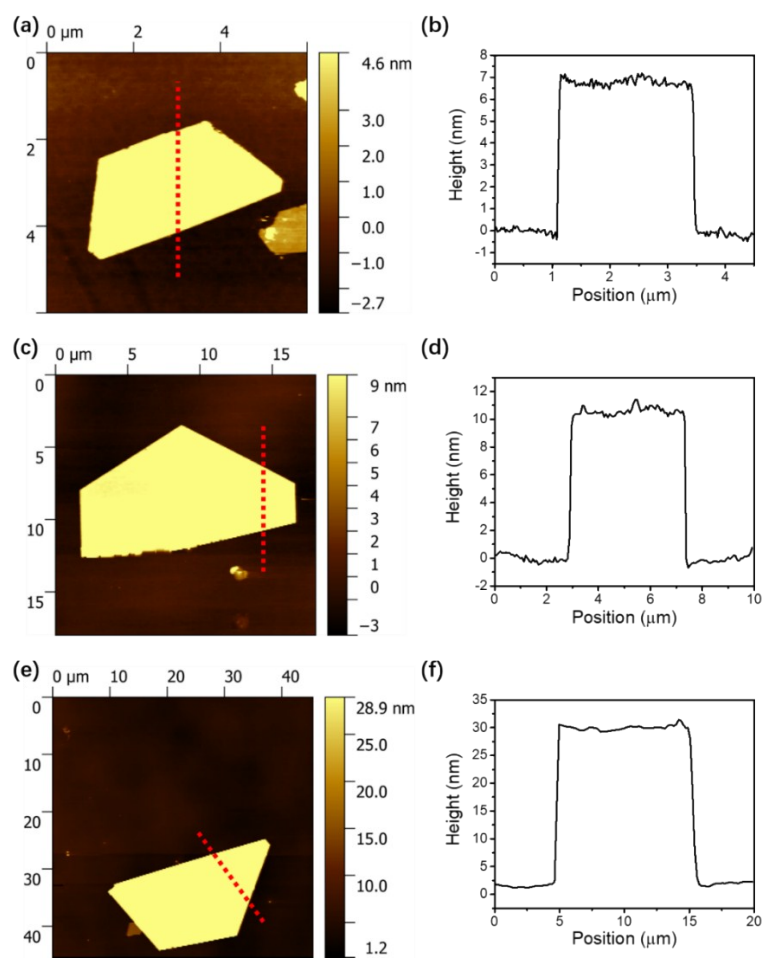
$$R_\lambda = I_{ph}/PS$$

$$EQE = hcR_\lambda/e\lambda$$

where  $I_{ph} = I_{photo} - I_{dark} = 1.38 \mu\text{A}$  is the photocurrent,  $I_{photo}$  and  $I_{dark}$  are the currents with and without laser illumination,  $P$  is the incident light intensity,  $S = 1488 \mu\text{m}^2$  is the effective illuminated area,  $h$  is Planck's constant,  $e$  is the electronic charge and  $\lambda = 532 \text{ nm}$  is the wavelength of incident light. Thus,  $R_{\lambda}$  and the EQE of our device are  $31 \text{ AW}^{-1}$  and  $7.7 \times 10^3 \%$ , respectively.

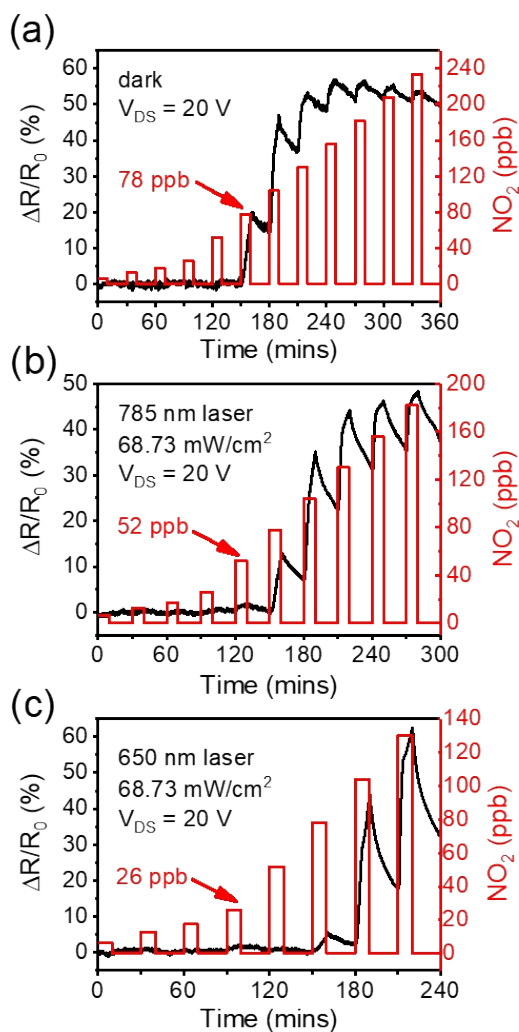


**Figure S1:** Optical images of semi-hexagonal SnS<sub>2</sub> nanosheets with different lateral dimensions.

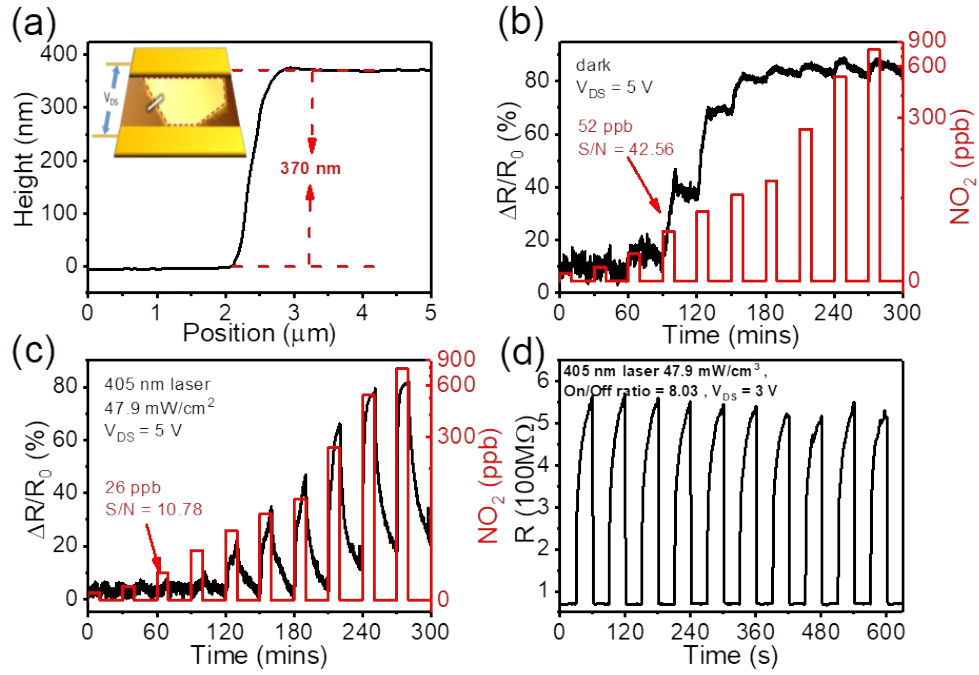


**Figure S2:** (a, c, e) Three examples of AFM images of semi-hexagonal SnS<sub>2</sub> nanosheets. (b, d, f) Corresponding height profiles of the dashed line shown in (a, c, e).

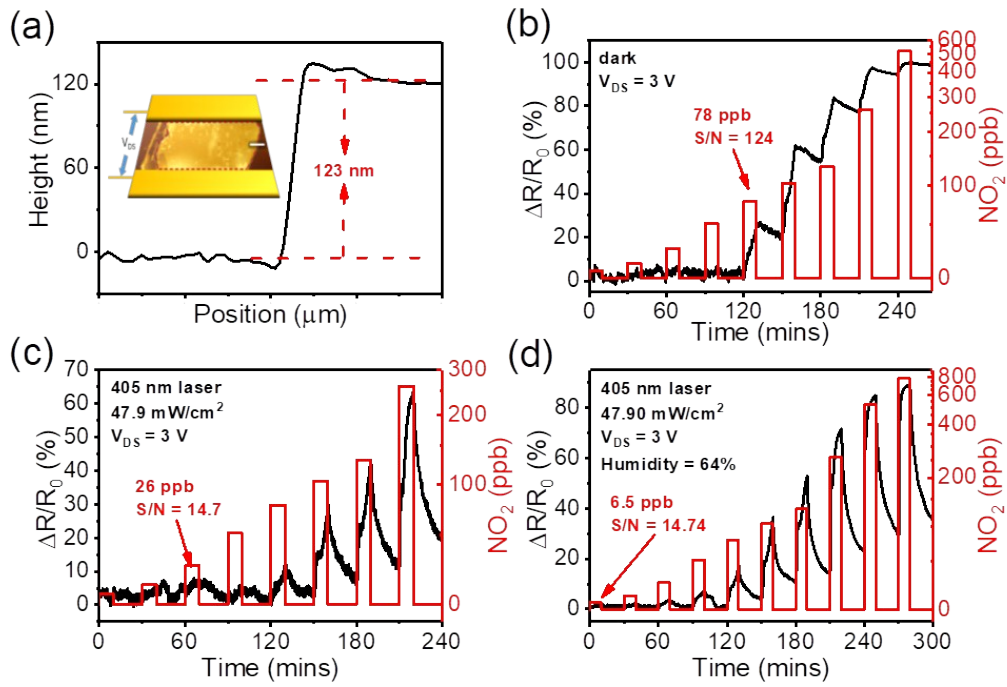




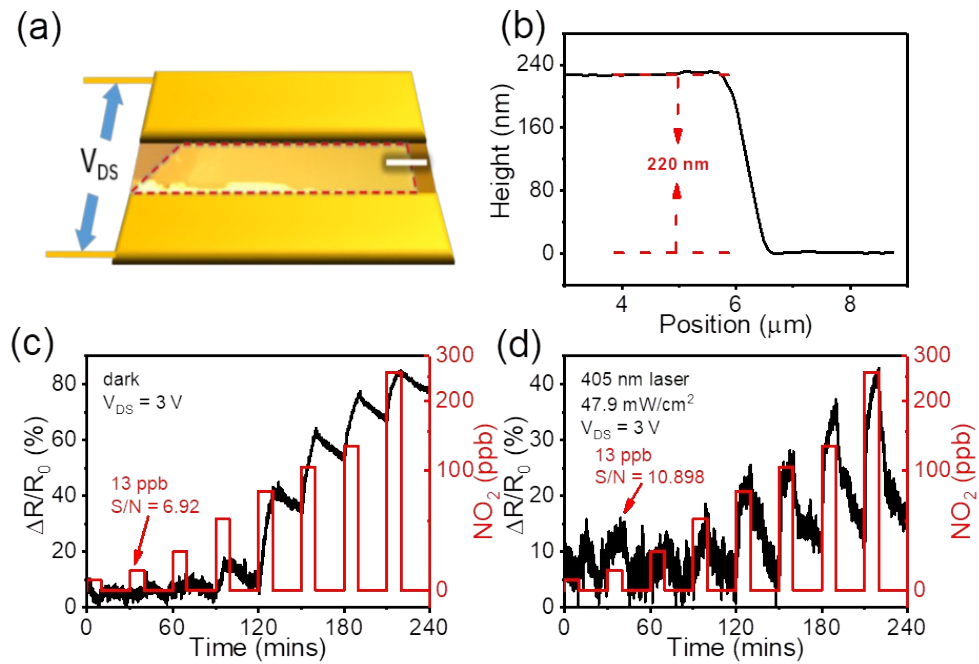
**Figure S3:** Dynamic sensing response of  $\Delta R/R_0$  change versus time for the SnS<sub>2</sub>-based sensor upon exposure to NO<sub>2</sub> gas with concentrations ranging from 6.5 ppb to 130 ppb in the dark (a) and under 785 nm (b) and 650 nm (c) laser irradiation.



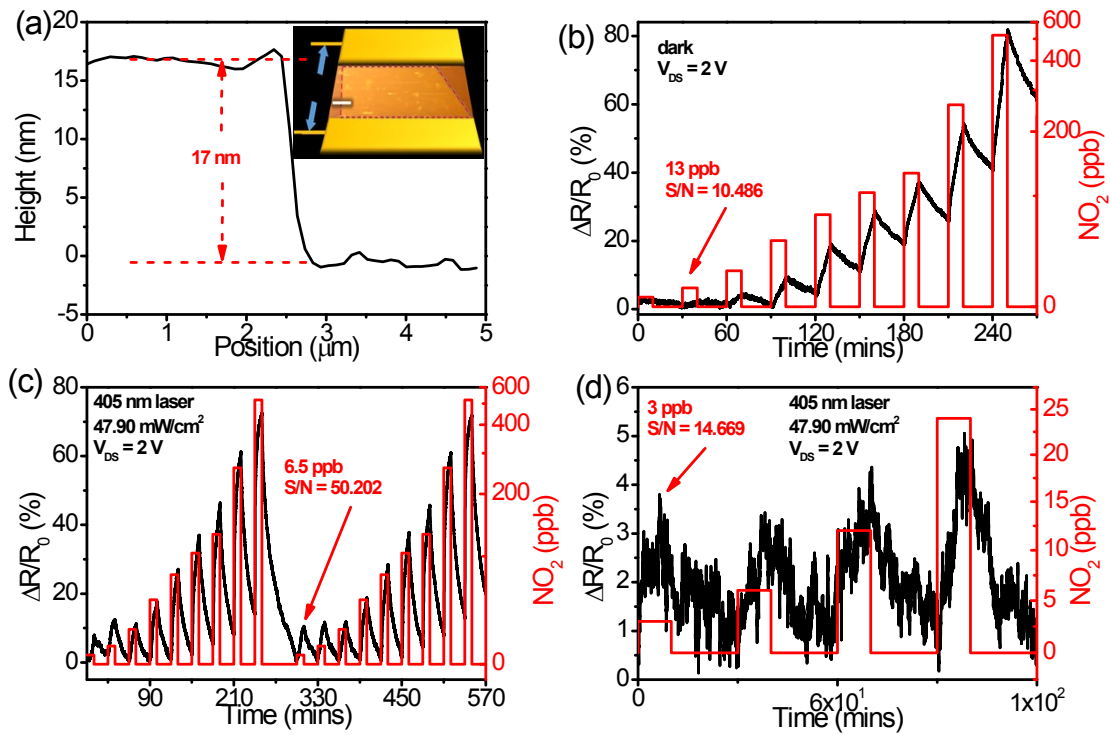
**Figure S4.** (a) Height profile of SnS<sub>2</sub> sample-1 along the white line in the inset AFM image. Dynamic sensing response of  $\Delta R/R_0$  change versus time for the sensor upon exposure to NO<sub>2</sub> gas with different concentrations under (b) dark environment and (c) 405 nm laser irradiation. (d) The time-resolved photon response measured with on/off ratio of 8.



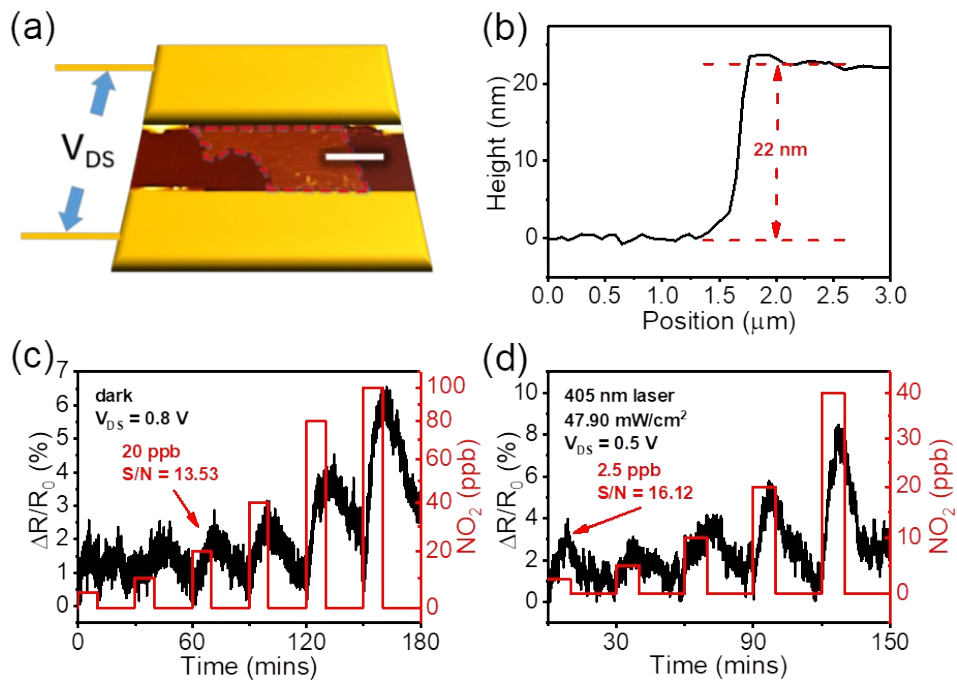
**Figure S5.** (a) Height profile of SnS<sub>2</sub> sample-2 along the white line in the inset AFM image. Dynamic sensing response of  $\Delta R/R_0$  change versus time for the sensor upon exposure to NO<sub>2</sub> gas with different concentrations under (b) dark environment, (c) 405 nm laser irradiation and (d) 64% humidity with 405 nm laser irradiation.



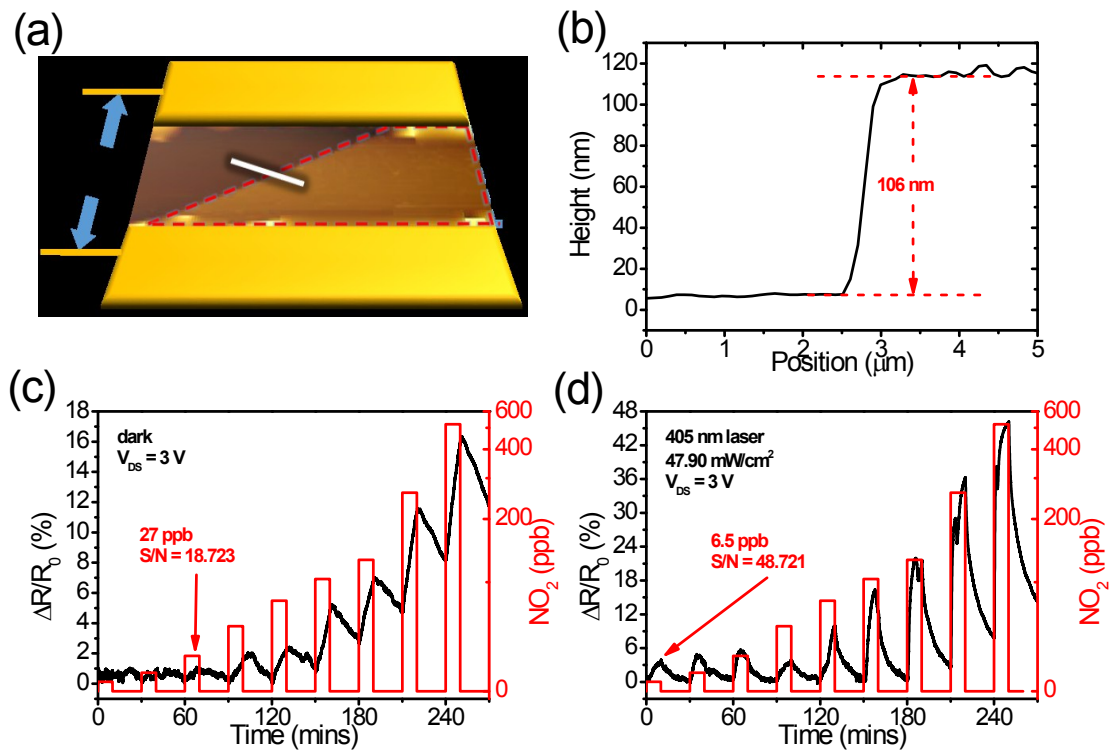
**Figure S6.** (a) The AFM image of SnS<sub>2</sub> sample-3. Corresponding to the white line in (a), the height profile was showed in (b). Dynamic sensing response of  $\Delta R/R_0$  change versus time for the sensor upon exposure to NO<sub>2</sub> gas with different concentrations under (c) dark environment and (d) 405 nm laser irradiation.



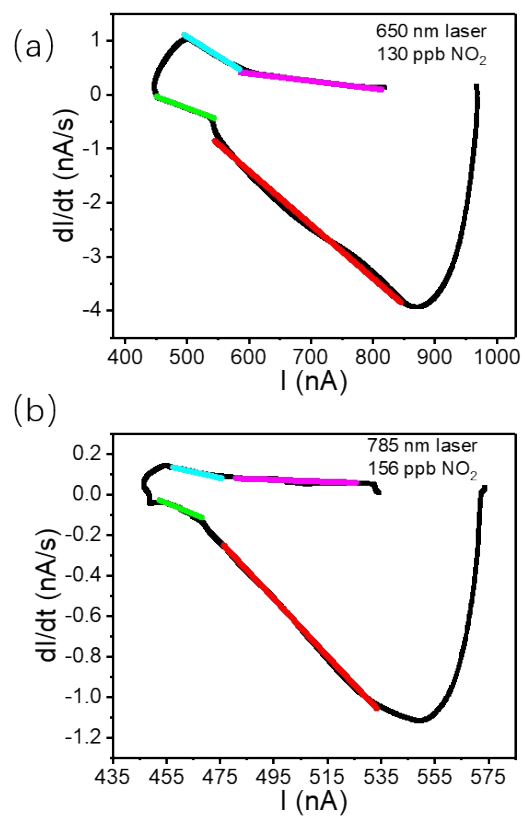
**Figure S7.** (a) Height profile of SnS<sub>2</sub> sample-4 along the white line in the inset AFM image. Dynamic sensing response of  $\Delta R/R_0$  change versus time for the sensor upon exposure to NO<sub>2</sub> gas with different concentrations under (b) dark environment and (c, d) 405 nm laser irradiation. (c) A stability test of repeating NO<sub>2</sub> concentration changing from 6.5 to 580 ppb for two times.



**Figure S8.** (a) The AFM image of SnS<sub>2</sub> sample-5. Corresponding to the white line in (a), the height profile was showed in (b). Dynamic sensing response of  $\Delta R/R_0$  change versus time for the SnS<sub>2</sub> sample-6 sensor upon exposure to NO<sub>2</sub> gas with different concentrations under (c) dark environment and (d) 405 nm laser irradiation.

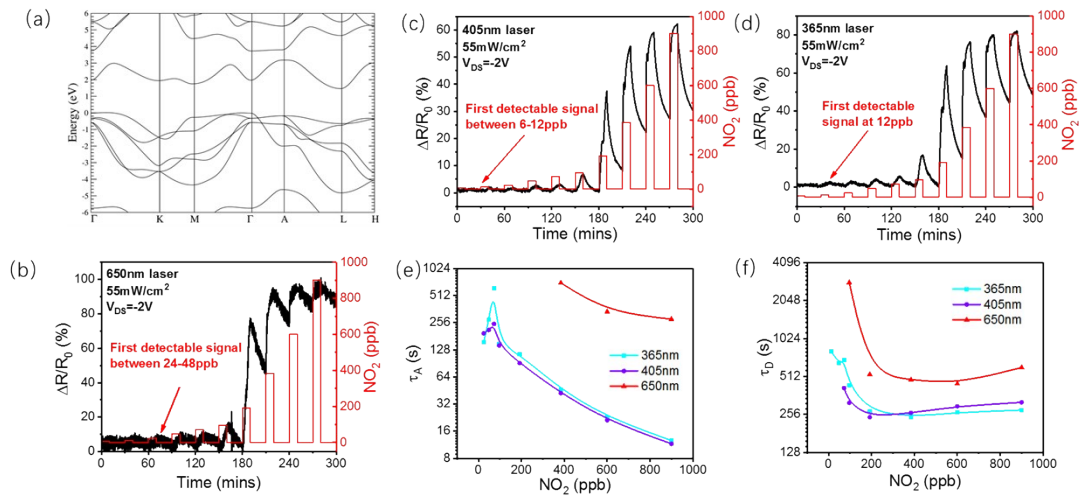


**Figure S9.** (a) The AFM image of SnS<sub>2</sub> sample-6. Corresponding to the white line in (a), the height profile was showed in (b). Dynamic sensing response of  $\Delta R/R_0$  change versus time for the sensor upon exposure to NO<sub>2</sub> gas with different concentrations under (c) dark environment and (d) 405 nm laser irradiation.



**Figure S10.** (a) The  $dI/dt$ - $I$  curve of 130 ppb  $\text{NO}_2$  test under 650 nm laser illumination. (b) The  $dI/dt$ - $I$  curve of 156ppb  $\text{NO}_2$  test under 785 nm laser illumination.





**Figure S11.** (a) Calculated band structure of  $\text{SnS}_2$ . Gas sensing laser performance of another sensor under (b) 365 nm, (c) 405 nm, and (d) 650 nm laser illuminations. (e) Absorption time and (f) desorption time as a function of gas concentration.

Reference:

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